

<b>INFORMATION DISCLOSURE STATEMENT</b> (Use several sheets if necessary)	Atty. Docket No. FIS920030196US1 (16715)	Serial No. Unassigned
	Applicant Wu-Sung Huang	
	Filing Date Herewith	Group Unassigned


**U.S. PATENT DOCUMENTS**

EXAMINER'S INITIAL*	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (if appropriate)
SJL	6,527,966 B1	03/04/03	Shimomura et al.	216	41	
	6,468,718 B1	10/22/02	Kang et al.	430	281-1	
	6,420,088 B1	07/16/02	Angelopoulos et al.	430	272.1	
	6,270,948 B1	08/07/01	Sato et al.	430	314	
	6,114,085	09/05/00	Padmanaban et al.	430	270.1	
	6,087,064	07/11/00	Lin et al.	430	270.1	
	6,025,117	02/15/00	Nakano et al.	430	314	
	5,641,849	06/24/97	Nishida et al.	528	10	
	5,554,485	09/10/96	Dichiara et al.	430	271.1	
	5,380,621	01/10/95	Dichiara et al.	430	272.1	
	4,891,303	01/02/90	Garza et al.	430	312	

**FOREIGN PATENT DOCUMENTS**

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

**OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)**


EXAMINER 	DATE CONSIDERED 9-18-05
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\* EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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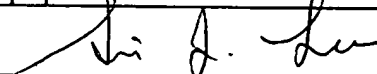
EXAMINER'S INITIAL*	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (if appropriate)

**FOREIGN PATENT DOCUMENTS**

EXAMINER'S INITIAL*	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
SJL	1 JP2002164347A	02/20/02	Japan				
	2						
	3						

**OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)**

SJL	Y. Matzuura, et al., "Synthesis of Polysilane-Acrylic Copolymers by Photopolymerization and Their Application to Positive Resists for EB Lithography", <u>Journal of Photopolymer Science and Technology</u> , No. 2, 14: 175-180; (2001).

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